ABSTRACT

A positive-type photosensitive resin composition includes (A) an alkali-soluble resin, (B) a photosensitizer, and (C) a silicon compound shown by the following general formula (1).

$$(R_2O)_3—Si—R_1—Si—(OR_2)_3 \quad (1)$$

wherein R_1 represents an alkylene group having 5 to 30 carbon atoms or an organic group that includes at least one aromatic ring, and R_2 represents an alkyl group having 1 to 10 carbon atoms. The positive-type photosensitive resin composition exhibits excellent storage stability, produces a film that exhibits excellent adhesion to a substrate during development, and produces a cured film that exhibits excellent adhesion to a substrate after humidification.